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Substitute for form 1449A/PTO				Complete if Known		
INFO	RMATION	I DISCLO	SURE	APPLICATION NUMBER	10/747,737	
STATEMENT BY APPLICANT				FILING DATE	12/29/2003	
				FIRST NAMED INVENTOR	Bailey et al.	
(use as many sheets as necessary)				Group Art Unit	1756	
Sheet	6	of	7	Examiner Name	Unassigned	
				Attorney Docket Number	PA97-39D13D21 ·	

UINEK PKK		NON PATENT LITERATURE DOCUMENTS	72		
Examiner Initials*	Cita No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.			
EC	C88	Colburn et al., Step and Flash Imprint Lithography: A New Approach to High-Resolution Patterning, Proc. Of SPIE, vol. 3676, 3/1/1999			
	C87	Heldari, Nanoimprint Lithography at the 6 in. Wafer Scale, J. Vac. Sci. Technol. B 18(6), pp. 3557 - 3560, 11/1/2000			
	+	Translation of Japanese Patent 02-92603	Т		
	C88	4/3/90			
	1	Translation of Japanese Patent 02-24848	T		
	C69	1/26/AD			
	C70	Chou et al., Ultrafast and Direct Imprint of Nanostructures in Silicon, Nature, Col. 417, (June 2002), pp. 835-837, 6/1/2002			
	C71	Chou et al., Nanoimprint Lithography, Journal of Vacuum Science Technology B 14(16), pp. 4129-4133, 11/1/1998			
	C72	Colburn et al., Development and Advantages of Step-and-Flash Lithography, Solid State Technology, 7/1/2001			
	C73	Colburn et al., Characterization and Modeling of Volumetric and Mechanical Properties for Step and Flash Imprint Lithography Photopolymers, Journal of Vacuum Science Technology. Vol b. 19(6), 11/1/2001			
EL	C74	Bailey et al., Step and Flash Imprint Lithography: Defect Analysis, Journal of Vacuum Science, B 19(6), pp. 2808-2810, 11/1/2001			

Examiner Signature	bel	Date Considered	5/15/06

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OTHER PRIOR	R ART -	NON PATENT LITERATURE DOCUMENTS	
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EC	C75	Bailey et al., Step and Flash Imprint Lithography: Template Surface Treatment and Defect Analysis, Journal of Vecuum Science, B 18(6), pp. 3572-3577, 11/1/2000	
		Schneider et al., Stripes of Partially Fluorinated Alkyl Chains: Dipolar Langmuir Monolayers	
EC	C78	5/1/05	
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